

Title (en)  
METHOD FOR MANUFACTURING METAL CATALYST HAVING INORGANIC FILM DEPOSITED THEREON BY MEANS OF ALD PROCESS INTO WHICH MAINTENANCE STEP IS INTRODUCED, AND METAL CATALYST MANUFACTURED THEREBY

Title (de)  
VERFAHREN ZUR HERSTELLUNG EINES METALLKATALYSATORS MIT DARAUFGESCHIEDENEM ANORGANISCHEM FILM MITTELS ALD-VERFAHREN UND DAMIT HERGESTELLTER METALLKATALYSATOR

Title (fr)  
PROCÉDÉ DE FABRICATION D'UN CATALYSEUR MÉTALLIQUE SUR LEQUEL EST DÉPOSÉ UN FILM INORGANIQUE AU MOYEN D'UN PROCÉDÉ ALD DANS LEQUEL UNE ÉTAPE DE MAINTENANCE EST INTRODUITE, ET CATALYSEUR MÉTALLIQUE AINSI FABRIQUÉ

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Abstract (en)  
The present invention relates to a method for manufacturing a metal catalyst having an inorganic film deposited thereon using an atomic layer deposition (ALD) process. More specifically, the present invention aims to provide optimal process conditions by introducing a maintenance step into an ALD process. Accordingly, it is possible to uniformly deposit the inorganic film even on the internal structure of a porous catalyst and to provide excellent catalytic activity and sintering prevention effect.

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